



International Advanced Wafer Geometry TF Report for Silicon Wafer Committee

Yoshise, AWG TF Leader
Dec 17, 2015 Semi Japan Office

Agenda

A.	ADMINISTRATIVE ISSUES		1:30 PM
	1) Introductions and Announcements	Akiyama	1:30 PM
	2) Anti Trust Reminder	Akiyama	1:32 PM
	3) Intellectual Property Policy	Akiyama	1:34 PM
	4) Effective Meeting Guidelines	Akiyama	1:36 PM
B.	REVIEW OF PRIOR MEETING AND WORKING GROUPS		1:38 PM
	1) Review of recent European activities	Passek	1:38 PM
	2) Review of recent North America activities	Poduje	1:43 PM
C.	BALLOT Development		1:48 PM
	1) Doc 5744A, line item revision for M49-1014, for exclusion windows.	Yoshise/Haller	1:48 PM
D.	Presentations		2:18 PM
			2:18 PM
E.	Reports		2:18 PM
			2:18 PM
G.	Old Business		2:18 PM
			2:18 PM
	New Business		2:18 PM
H.			2:18 PM
	ACTION ITEMS		2:18 PM
	1) From this meeting	Akiyama	2:18 PM
			2:20 PM
I.	FUTURE MEETINGS & AGENDA ITEMS		2:20 PM
	AWG TF, NA Spring Meeting		2:20 PM
			2:25 PM
J.	ADJOURN		2:25 PM

Attendee 13 attendees (3 via phone)

Name	Company		Name	Company	
Toda	SEH	yes	F Riedel	Siltronic	
R Takeda	G Wafers Japan	yes	N Poduje	SMS	Phone
M Goldstein	Intel		A Shinoda	KLA-Tencor	
H Hashizume	Kobelco Research		J Sinha	Self	Phone
M Ikota	Hitachi Hitech	yes	T Takenaka	Consultant	
J Valley	SunEdison		T Nakai	SUMCO	yes
K Naoi	Kuroda Precision		S Kumai	Consultant	yes
M Bullis	Material & Metrology		Y Tamaki	ATMI	
N Kawai	Self	yes	K Izunome	Global Wafers	
F Passek	Siltronic	yes	P Lin	G450C	
P Wagner	Self		K Lee	G450C	
K Haller	KLA-Tencor	phone	S Akiyama	Raytex Optima (Meeting Leader)	yes
S Ito	Kuroda Precision	yes	M Yoshise	Self (Meeting Leader)	yes
K Araki	G Wafer		J Collins	SEMI Staff	

Liaison Report

1. European Activities by Dr. Fritz Passek, Siltronic



Microsoft
PowerPoint 97-2003 Presentation

2. N.A. Activities by N Poduje, SMS



Microsoft Word
7 - 2003 Document

Ballot Development

Revision to M49

1. Back ground

- At SEMICON West 2014. SNARF of 5744 as line item was approved with clarification “Exclusion Windows” and other related update.
 - Changes
 - Add definition of the windows
 - List up the applicable windows to be excluded.
 - Update the item 3.4 in table 3 and table 4
- Balloted at Cycle 4 2015
- Adjudicated at SEMICON West 2015→ Failed
- Discussed at Dresden Oct 2015
 - Develop new document based on draft from Dresden meeting.
 - K Haller brought proposal for new description

Ballot Development

Revision to M49 for Exclusion Windows

1. Back ground

- At SEMICON West 2014. SNARF of 5744 as line item was approved for clarification “Exclusion Windows” and other related update.
 - Changes
 - Add definition of the windows
 - List up the applicable windows to be excluded.
 - Update the item 3.4 in table 3 and table 4
- Balloted at Cycle 4 2015
- Adjudicated at SEMICON West 2015→ Failed
- Discussed at Dresden Oct 2015
 - Develop new document today based on draft from Dresden meeting.
 - K Haller brought proposal for new description

Ballot Development

Revision to M49 for Exclusion Windows

2. Discussion Points

1. Add newly definition of exclusion windows which for Laser Mark, Fiducial Notch, Wafer handling contacts at section 4 Terminology.
2. Rewrite recommended specification at section 3.4 in both table3 and 4.
3. Other related update

3. Discussion

–Based on draft from previous meeting at Dresden in Oct TF modified some with Kurt Haller's of KT suggestion

4. Changes are



M49 Ballot
160229

5. Propose to be approved at Silicon Committee on Dec 17th at appropriate ballot cycle for adjudication at Semicon West 2016.
6. →Approved to ballot & Submitted for cycle 3

Action items

1. Bring Doc 5744A to Silicon committee on Dec 17th.
→ Yoshise → Done for Cycle 3
2. Revision to SEMI Standard M78 Guide for determining Nanotopography to add adjusting filter size and analysis area by Gerd Pfeiffer IBM.
Gerd left IBM and move to Global Foundry. So he might no longer be responsible for such SEMI activities
→ K Haller KT to confirm → Confirmed
3. John Valley presented new nanotopography for litho purpose using thickness base data at Semicon West. Need to confirm he wants to proceed the discussion for standardization. The activities for this new topic required co-work with KT then need to check with KT.
→ By Yoshise and Kurt → No action required
4. Next meeting, NA Spring meeting, April 2016 at